## CLAIMS

WHAT IS CLAIMED IS:

1. A blank mask comprising:

a transparent substrate and a light shielding film disposed on the transparent substrate,

wherein the light shielding film comprises a transition metal and at least one of oxygen and nitrogen, and

wherein the light shielding film has an SA1 value of 60 to 90 mN/m according to Equation 1-1:

[Equation 1-1]

$$SA1 = \gamma_{SL} \times tan\theta$$

where, in the Equation 1-1, the $\gamma_{SL}$ is an interfacial energy between the light shielding film and a pure water and θ is a contact angle of the light shielding film measured with the pure water.

2. The blank mask of claim 1,

wherein the θ is 70 ° or more.

3. The blank mask of claim 1,

wherein the $\gamma_{SL}$ is 22 mN/m or more.

4. The blank mask of claim 1,

wherein the light shielding film has a surface energy of 42 to 47 mN/m.

5. The blank mask of claim 4,

wherein the light shielding film has a ratio of 0.135 to 0.16 for polar component of the surface energy compared to the surface energy of the light shielding film.

6. The blank mask of claim 1,

wherein the light shielding film comprises a first light shielding layer and a second light shielding layer disposed on the first light shielding layer.

7. The blank mask of claim 6,

wherein an amount of the transition metal of the second light shielding layer is greater than an amount of the transition metal of the first light shielding layer.

8. The blank mask of claim 1,

wherein the transition metal comprises at least one selected from the group consisting of Cr, Ta, Ti, and Hf.

9. A photomask comprising:

a transparent substrate and a light shielding pattern film disposed on the transparent substrate,

wherein the light shielding pattern film comprises a transition metal and at least one of oxygen and nitrogen, and

wherein the light shielding pattern film has a PSA1 value of 60 to 90 mN/m according to Equation 3 below:

[Equation 3]

$$PSA1 = \gamma_{PSL} \times tan\theta_p$$

where, in the Equation 3, $\gamma_{PSL}$ is an interfacial energy between an upper surface of the light shielding pattern film and a pure water and $\theta_P$ is a contact angle of the upper surface of the light shielding pattern film measured with the pure water.

10. The photomask of claim 9,

wherein the light shielding pattern film comprises a first light shielding layer and a second light shielding layer disposed on the first light shielding layer.

11. The photomask of claim 10,

wherein an amount of the transition metal of the second light shielding layer is greater than an amount of the transition metal of the first light shielding layer.

12. The photomask of claim 9,

wherein the transition metal comprises at least one selected from the group consisting of Cr, Ta, Ti, and Hf.